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(21) International Application Number: PCT/KR98/00272 (22) International Filing Date: 3 September 1998 (03.09.98) (30) Priority Data: 1998/30108 27 July 1998 (27.07.98) KR (71) Applicant: ENEX CO., LTD. [KR/KR]; 809-10, Yeok-sam-Dong, Kangnam-Ku, Seoul 135-080 (KR). (72) Inventors: LEE, Yong, Hee; Building 206-509, Tongmyoung Apt., Sunbu-Dong, Ansan, Kyunggi-Do 425-140 (KR). PARK, Jin, Kyu; 734-7, Banpo 1-Dong, Seocho-Ku, Seoul 137-041 (KR). PARK, Jin, Ho; 95-29, Heukseok 3-Dong, Dongjak-Ku, Seoul 156-071 (KR). (74) Agent: KIM, Seong, Taik; 148-28, Ulchiro 2-Ka, Chung-Ku, Seoul 100-192 (KR).		(81) Designated States: AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, CH, CU, CZ, DE, DK, EE, ES, FI, GB, GE, GH, GM, HR, HU, ID, IL, IS, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MD, MG, MK, MN, MW, MX, NO, NZ, PL, PT, RO, RU, SD, SE, SG, SI, SK, SL, TJ, TM, TR, TT, UA, UG, UZ, VN, YU, ZW, ARIPO patent (GH, GM, KE, LS, MW, SD, SZ, UG, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG). Published With international search report.

(54) Title: METHOD AND APPARATUS FOR CLEANING HARMFUL GAS BY IRRADIATION WITH GAS LASER AND ELECTRON BEAMS

(57) Abstract

An apparatus (10) for reducing harmful ingredients in gas by irradiating the gas with an electron beam. The apparatus (10) comprising a voltage generating unit adapted to generate a high-frequency and high voltage signal, and a reaction unit (100) coupled to the voltage generating unit to receive the high-frequency and high voltage signal, the reaction unit (100) including an electron beam pole having a plurality of openings along the surface of the electron beam pole, and a plurality of discharge cells for each opening, the discharge cells being disposed to face the corresponding opening for generation of the electron beam therebetween, the region between the discharge cells and the openings defining a reaction region through which the gas travels.

